

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	64699	(etch\$3 same (silicon or poly adj silicon)) same mask\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 08:43
L2	4250	1 same ((hard near mask\$3) same (oxide or nitride))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 08:43
L3	1509	2 same photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 09:42
L4	1070	3 and @pd<"20040714"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 09:50
L5	13	4 and ((micro near trench\$3) or (trench\$3 near effect))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 08:45
L6	4076	(etch\$3 same (hard near mask\$3)) same photoresist	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 09:21
L7	2	6 same (trench\$3 near effect)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 09:25
L8	0	chung-henry.in. and (trench\$3 near effect)	US-PGPUB; USPAT	OR	OFF	2005/12/03 09:26
L9	41	chung-henry.in.	US-PGPUB; USPAT	OR	OFF	2005/12/03 09:31
L10	7	chung-henry.in. and ((hard near mask\$3) same photoresist)	US-PGPUB; USPAT	OR	OFF	2005/12/03 09:27
L11	8	chung-henry.in. and (hard near mask\$3)	US-PGPUB; USPAT	OR	OFF	2005/12/03 09:31
L12	1	11 not 10	US-PGPUB; USPAT	OR	OFF	2005/12/03 09:31

L13	0	2 same (reduc\$3 near2 pitch)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 09:43
L14	9	3 and (micro near trench\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 10:53
L15	8	3 and (trench\$3 near effect)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/03 10:56
L16	0	438/947.ccls. and (trench\$3 near effect)	US-PGPUB; USPAT	OR	OFF	2005/12/03 10:57
L17	4	438/947.ccls. and 3	US-PGPUB; USPAT	OR	OFF	2005/12/03 10:57